



STFW

ASA-481-10

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

N. HASEGAWA et al.

Serial No. 10/777,060

Group Art Unit: 1756

Filed: February 13, 2004

Examiner: Unassigned

For: PHOTOMASK AND PATTERN  
FORMING METHOD EMPLOYING  
THE SAME

INFORMATION DISCLOSURE STATEMENT (IDS)  
UNDER § 1.97 AND § 1.98

Commissioner for Patents  
Mail Stop DD  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

1. This IDS should be considered:

when filed within three months of the filing date of the present application, or within three months of the filing date of the National Stage as set forth in § 1.491 in an international application, or before the mailing date of a first Office Action on the merits, whichever occurs last;

2. Listing of the information submitted is on the attached Form PTO-1449, which forms a part of this IDS. A copy of each listed document is enclosed when needed (needed for U.S. and foreign patents, publication or portion thereof listed; no copy of a U.S. patent application is needed; a copy of a document is not needed when previously submitted or previously cited by the PTO in a parent application of the present application as set forth under 35 U.S.C. § 120).

3. The undersigned hereby states:

(a) that each item of information contained in this IDS was first cited in any communication from a foreign patent office in a counterpart foreign application, as indicated on the copy of the communication submitted herewith, which communication was dated not more than three months prior to the filing of this IDS; or


☒ (b) that no item of information contained in this IDS was cited in a communication from a foreign patent office in a counterpart foreign application or, to the knowledge of the undersigned after making reasonable inquiry, was known to any individual designated in § 1.56(c) more than three months prior to the filing of this IDS.

4. If a fee or additional fee is required, the Commissioner is hereby authorized to charge any fee or additional fee that may be required and credit any excess to Deposit Account No. 50-1417.

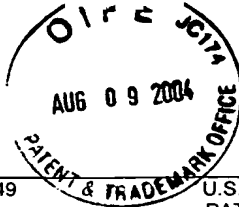
5. No explanation of relevancy is being provided for the following document(s) because each is either in the English language, discussed in the present Specification, or its relevance is as stated in a communication from a foreign patent office in a counterpart foreign application.

6. If the PTO determines that part(s) of the required content is inadvertently omitted, then it is requested that the Applicant(s) be given additional time and specific identification of such omission(s) to enable full compliance.

Respectfully submitted,

  
Daniel J. Stanger  
Registration No. 32,846  
Attorney for Applicants

MATTINGLY, STANGER & MALUR, P.C.  
1800 Diagonal Road, Suite 371  
Alexandria, Virginia 22314  
Telephone: (703) 684-1120  
Facsimile: (703) 684-1157  
Date: August 9, 2004



FORM PTO-1449 (REV. 7-80)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. ASA-481-10	SERIAL NO. 10/777,060
<b>LIST OF DOCUMENTS CITED BY APPLICANT</b> (Use several sheets if necessary)		APPLICANT N. HASEGAWA et al.	
		FILING DATE February 13, 2004	GROUP 1756

**U.S. PATENT DOCUMENTS**

* EXAMINER INITIAL	DOCUMENT	DATE	NAME	CLASS	SUBCLASS	FILING DATE (If Appropriate)
	AA					
	AB					
	AC					
	AD					
	AE					
	AF					
	AG					
	AH					
	AI					
	AJ					
	AK					

**FOREIGN PATENT DOCUMENTS**

	DOCUMENT	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
	AL					<input type="checkbox"/>	<input type="checkbox"/>
	AM					<input type="checkbox"/>	<input type="checkbox"/>
	AN					<input type="checkbox"/>	<input type="checkbox"/>
	AO					<input type="checkbox"/>	<input type="checkbox"/>
	AP					<input type="checkbox"/>	<input type="checkbox"/>

**OTHER DOCUMENTS** (Including Author, Title, Date, Pertinent Pages, etc.)

	AR	Watanabe, et al., "Transparent Phase Shifting Mask"; IEDM Technical Digest. International Electron Devices Meeting 1990, pp. 821-824.
	AS	Terasawa, et al., "Imaging Characteristics of Multi-Phase-Shifting and Halftone Phase-Shifting Masks." Japanese Journal of Applied Physics, Vol. 30, No. 11B (1991), pp. 2991-2997.
	AT	

EXAMINER	DATE CONSIDERED
----------	-----------------

\* EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.